

REMARKS

Entry of the foregoing and reconsideration of the application identified in caption, as amended, pursuant to and consistent with 37 C.F.R. §1.114 and in light of the remarks which follow, are respectfully requested.

By the above amendments, new dependent claim 29 has been added which recites that the thickness of the low refractive index layer is about 100 nm. Support for such new claim can be found in the specification at least at page 28, lines 17-19 and page 31, line 2. New dependent claim 30 recites that the at least one inorganic fine particle having an average particle size of 30 to 100% of the thickness of the low refractive index layer, is a hollow silica fine particle. Support for such new claim can be found in the specification at least at page 29, lines 13-15. Entry of the above amendments is proper at least because a Request for Continued Examination is being filed herewith. See 37 C.F.R. §1.114.

In the Official Action, claims 15-18, 22-25 and 27 stand rejected under 35 U.S.C. §103(a) as being obvious over U.S. Patent No. 6,383,559 (*Nakamura et al*) in view of U.S. Patent No. 5,909,314 (*Oka et al*). Claim 19 stands rejected under 35 U.S.C. §103(a) as being obvious over *Nakamura et al* in view of *Oka et al* and further in view of U.S. Patent No. 6,210,858 (*Yasuda et al*). Claims 20 and 21 stand rejected under 35 U.S.C. §103(a) as being obvious over *Nakamura et al* in view of *Oka et al* and further in view of U.S. Patent No. 6,254,973 (*Yoshida et al*). Claim 26 stands rejected under 35 U.S.C. §103(a) as being obvious over *Nakamura et al* in view of *Oka et al* and further in view of U.S. Patent No. 6,633,352 (*Yamaguchi et al*) and U.S. Patent No. 6,181,400 (*Yang*). Claim 28 stands rejected under 35 U.S.C. §103(a) as being obvious over *Nakamura et al* in view of *Oka et al* and further in view of U.S. Patent No. 6,633,352 (*Yamaguchi et al*). Withdrawal of the above rejections is respectfully requested for at least the following reasons.

Nakamura et al does not disclose or suggest each feature recited in independent claim 15. For example, as previously acknowledged by the Patent Office, *Nakamura et al* does not disclose or suggest a low refractive index layer that comprises at least one silica fine particle having a particle size of less than 25% of the thickness of the low refractive index layer, as recited in claim 15.

As discussed in Applicants' previous response, one of ordinary skill in the art would not have been motivated to employ the inorganic fillers of *Oka et al* in the low refractive index layer of *Nakamura et al*. In this regard, in the Advisory Action at pages 2-3, the Patent Office has taken the following position:

When the volume fraction of the micro-voids is low, the amount of inorganic micro particles is low in the low refractive index layer of Nakamura, and hence the fine silica particles of Oka is [sic] needed to prevent settling of the inorganic micro particles in the low refractive index layer of Nakamura.

However, the Patent Office has relied on *Nakamura et al* for disclosing the densely packed configuration of micro particles shown in Figure 1 to show that the average particle size is 50% of the thickness of the low refractive index layer (Official Action dated October 17, 2006 at page 2). It is this densely packed configuration that the Patent Office has alleged corresponds to the claimed antireflection film. Clearly, in view of the densely packed configuration of micro particles relied upon by the Patent Office, one of ordinary skill in the art would not have been motivated to attempt to prevent settling of the particles forming the densely packed configuration.

Moreover, *Nakamura et al* unequivocally discloses that a relatively low volume fraction of the micro voids can be obtained without any mention that inorganic fillers are "needed" to obtain such low volume fraction (col. 12, lines 46-58). Respectfully, the Patent Office's assertion that the fine silica particles are necessary to obtain a relatively low volume fraction of the micro voids is a mischaracterization of the applied art.

Thus, in view of the above, it is apparent that *Oka et al* fails to cure the above-described deficiencies of *Nakamura et al*. Accordingly, withdrawal of the rejection based on the alleged combination of *Nakamura et al* and *Oka et al* is respectfully requested.

Yasuda et al, *Yoshida et al*, *Yamaguchi et al* and *Yang et al* have been relied on by the Patent Office for the reasons discussed at pages 6-11 of the Official Action dated October 17, 2006. However, like *Nakamura et al*, the above secondary applied documents fail to disclose or suggest a low refractive index layer that comprises at least one inorganic fine particle having an average particle size of 30 to 100% of the thickness of the low refractive index layer and at least one silica fine particle having a particle size of less than 25% of the thickness of the low refractive index layer, as recited in independent claim 15.

For at least the above reasons, it is apparent that no *prima facie* case of obviousness has been established. Accordingly, withdrawal of the §103(a) rejections is respectfully requested.

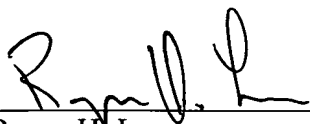
From the foregoing, further and favorable action in the form of a Notice of Allowance is believed to be next in order, and such action is earnestly solicited. If there are any questions concerning this paper or the application in general, the Examiner is invited to telephone the undersigned.

Respectfully submitted,

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